

Nano3 E-Beam Lithography Job Submission Form

Contact Information

Date	Name	P.I./Company	Phone	E-mail

Sample Information

Substrate	Thickness	Sample Size	Resist	Thickness	Number of Samples
Material Stack/Thickness (Starting from substrate up)					

Pattern and Layout Information

File Name			Critical Dimensions	Pattern Dimensions
Cell	Cells in X	Cells in Y	Pitch in X	Pitch in Y

E-beam Lithography Settings Information

(Please fill this section if you know the information)

Beam Current (nA)	Dose ($\mu\text{C}/\text{cm}^2$)	Resolution (nm)	Beam Step Size (nm)

Alignment Information (Only for Overlay/Mix Match Jobs)

(Please check Nano3 E-beam Lithography Guideline for help to fill this section)

Marker Shape		Marker Size		Marker Material		Marker Type	
						Positive	Negative
Global Marker Pitch		Global Marker Coordinates (Suppose layout center is (0,0))					
X	Y	LLC	LRC	ULC	URC		
Local Marker Pitch		Local Marker Coordinates (Suppose pattern center is (0,0))					
X	Y	LLC	LRC	ULC	URC		

(LLC = Lower Left Corner, LRC = Lower Right Corner, ULC = Upper Left Corner, URC = Upper Right Corner)

Billing Information

(For Nano3 staff only)

Accepted Date	Completion Date	Machine Time	Staff Time	Total Charge
Job #	Sample picked up by:		Date	